Macromolecules

Photopolymerization Kinetics and Dynamic Mechanical Properties 1 of Silanes Hydrolyzed without Evolution of Byproducts. 2

- Tetrakis[(methacryloyloxy)ethoxy]silane-Diethylene Glycol 3

Dimethacrylate 4

Mustafa Uygun,^{†,‡} Wayne D. Cook,^{*,†} Cornelis Moorhoff,[†] Fei Chen,[†] Claudia Vallo,[§] Yusuf Yagci,[‡] and 5 Marco Sangermano^{II} 6

- [†]Department of Materials Engineering, Monash University, Clayton, Victoria 3800, Australia 7
- [†]Department of Chemistry, Istanbul Technical University, Maslak 34469, Istanbul, Turkey 8
- [§]INTEMA, Universidad Nacional de Mar del Plata, Mar del Plata 7600, Argentina 9
- Department of Materials Science and Chemical Engineering, Politecnico di Torino, Torino 24-10129, Italy 10

ABSTRACT: The temperature dependence of photopolymer-12 ization kinetics of tetrakis[(methacryloyloxy)ethoxy]silane 13 (TetMESi) was compared with an analogue, diethylene glycol 14 dimethacrylate and their copolymers. In all cases, the kinetics 15 are controlled by the temperature dependence of the propaga-16 tion step, the effect of diffusion on radical termination, the effect 17 of rising glass transition during cure, and topological restraint 18 on complete conversion. The glass transition regions of these 19 polymers were very broad, suggesting their use in high tem-20 perature applications. NMR of the TetMESi monomer, and 21 FTIR and water sorption measurements during exposure to 22 water of the TetMESi-based polymers showed that the 23



Si-O-C bond was slowly hydrolyzed, resulting in water-swollen polymers containing poly(hydroxyethyl methacrylate) which reduced the glass transition temperature and narrowed the glass transition region. UV-vis spectroscopic studies showed that during exposure to water, SiO₂ nanoparticles or nanostructures were formed from the condensation of the silanol groups formed during the hydrolysis of TetMESi.

INTRODUCTION

24

25

26

27

Over the last three decades, hybrid inorganic-organic 29 materials have attracted increasing attention in the field of 30 material science due to their extraordinary properties, which 31 arise from the synergism between the properties of the compo-32 nents. Hybrid materials are classified as type-I and type-II 33 hybrids according to the interaction between inorganic and 34 organic moieties.¹ Type-I hybrids contain weak bonds such as 35 van der Waals, ionic, or hydrogen bonds, whereas type-II 36 37 hybrids contain strong covalent bonds. Hybrid materials have generally been produced by sol-gel processing through homo-38 geneous hydrolysis and condensation reactions of metal 39 alkoxides. 40

Silane based UV-curable monomers are widely used as pres-41 sure sensitive adhesives and weather resistant coatings due to 42 their low surface energy, low polarity, chemical inertness, and long-term weather resistance.^{2–4} However, the photopolymeri-43 44 zation kinetics of their formulations and the properties of the 45 cured products have scarcely been investigated. 46

In the sol-gel process, the gelation of metal-alkoxides, includ-47 48 ing silanes, involves two steps: hydrolysis of the metal-alkoxide

and condensation of the silanol groups $^{5-8}$ by either acid

$$(RO)_3SiOR + H_3O^+ \rightleftharpoons (RO)_3SiOH + H^+ + HOR$$

$$(RO)_{3}SiOH + H^{+} \rightleftharpoons (RO)_{3}SiO^{+} + H_{2}$$
$$(RO)_{3}SiO^{+}H_{2} + (HO)Si(OR)_{3} \rightarrow$$
$$(RO)_{2}Si - O - Si(OR)_{2} + H_{3}O^{+}$$

or base

$$(RO)_{3}SiOR + OH^{-} \rightleftharpoons (RO)_{3}SiOH + OR^{-}$$
$$OR^{-} + H_{2}O \rightleftharpoons HOR + OH^{-}$$
$$(RO)_{3}SiOH + OH^{-} \rightleftharpoons (RO)_{3}SiO^{-} + H_{2}O$$
$$(RO)_{3}SiO^{-} + (HO)Si(OR)_{3} \rightarrow$$
$$(RO)_{3}Si - O - Si(OR)_{3} + OH^{-}$$

Received: December 20, 2010 **Revised:** February 20, 2011

50

49

Macromolecules

In fairly strong acid catalyzed conditions, the condensation 51 52 (polymerization) process is faster than the hydrolysis reaction and so linear chains are initially formed, which then form an open 53 gel structure, whereas when fairly strong basic conditions are used, 54 the hydrolysis is faster than the condensation reaction and so 55 particles are formed.⁶ At low levels or in the absence of a catalyst, 56 this situation is less clear,⁹ but Brinker and Scherer⁷ conclude that 57 these conditions produce intermediate structures as originally 58 suggested by Schaefer and Keefer.¹⁰ 59

The conventional sol-gel process has several disadvantages 60 including a large volume shrinkage resulting from the removal of 61 solvents and small molecular byproducts of the hydrolysis and 62 polycondensation reactions such as water and alcohol. Recently a 63 number of researchers have addressed this $problem^{11-23}$ by 64 replacing the solvent-based alkoxides, such as methoxy and 65 ethoxy, with polymerizable alkoxide groups. Because this process 66 involves the polymerization of the hydroxyl monomer, the 67 volume shrinkage can be considerably reduced or eliminated. 68

There have been numerous studies of silanes containing a single 69 reactive functional group^{\perp} such as 3-(trimethoxysilyl)propyl 70 methacrylate²¹ or (3-glycidoxypropyl)trimethoxysilane^{24,25} but far 71 fewer investigations with silanes having three of four reactive groups. 72 Davidson et al.¹⁵ synthesized di- and tri(meth)acrylate silanes and 73 showed that they had high photopolymerization rates and suggested 74 their use as surface coatings. Novak and Davies¹¹ studied a tetra-75 acrylate silane suitable for the formation of highly uniform mono-76 lithic glasses and inorganic ceramic composite and monitored the 77 78 development of mechanical properties during their simultaneous photopolymerization and hydrolysis by water (20-40% in stoichio-79 metric excess) in the presence of NaF catalyst. According to these 80 workers¹¹ it was considered important that the photopolymeriza-81 tion and hydrolysis/condensation rates were comparable because 82 83 systems with faster hydrolysis/condensation rates were claimed to produce opaque, brittle glasses that shrink due to the evaporation of 84 unreacted monomer, whereas it was claimed that phase separation 85 of the monomer and water occurred with fast photopolymerization 86 rates causing loss of clarity. Kloosterboer and Touwslager²⁰ 87 patented the use of a tetra-acrylate silane for use in a liquid display 88 device and observed that the dynamic mechanical properties of the 89 polymerized material exhibited a broad glass transition region and 90 that after hydrolysis and drying the material was transparent. Some 91 other interesting multifunctional silane systems are those of Spange 92 and Grund²³ involving the cationic polymerization and cationic 93 hydrolysis/condensation of tetrafurfuryloxysilane and of spirobis-94 benzodioxasilane and by Novak^{12,13} on the ring-opening metathesis 95 polymerization of cyclic alkenylsilane monomers. 96

In this study, we report the polymerization kinetics and
dynamic mechanical properties of a silane based hybrid material,
namely tetrakis[(methacryloyloxy)ethoxy]silane, by itself and in
copolymerization with diethylene glycol dimethacrylate, and we
investigate their spectroscopy, water uptake, and viscoelastic
behavior in an aqueous environment.

103 **EXPERIMENTAL SECTION**

The tetrafunctional silane monomer studied was tetrakis[(methacry loyloxy)ethoxy]silane (TetMESi or 2-propenoic acid, 2-methyl-, silanetetrayltetrakis(oxy-2,1-ethanediyl) ester) and was prepared by our group in a manner similar to that described in the literature.¹⁵ Silicon tetrachloride was reacted with hydroxyethyl methacrylate (HEMA) at room temperature in anhydrous dichloromethane using a slight stoichiometric excess of pyridine to absorb the HCl generated. 120

121

122

123

124

125

126

127

128

129

130

131

132

133

134 SI





After 16 h, the dichloromethane was removed by rotary evaporation, and 111 the pyridinium hydrochloride salt was filtered off. ¹H NMR analysis with 112 a 300 MHz Bruker instrument in CDCl₃ gave the following peaks: δ = 113 1.895 (dd, J = 1.2, 1.5 Hz, 4×3 H), 3.966 (m, 4×2 H), 4.199 (m, $4 \times$ 114 2H), 5.523 (sm, 4×1H), 6.085 (sm, 4×1H) ppm. ¹³C NMR (75 MHz, 115 $CDCl_3$): $\delta = 18.26$ (Me), 61.92 (O—CH₂), 65.18 (O-CH₂), 125.72 116 (H₂C=), 136.22 (C=), 167.23 (C=O) ppm. The NMR analysis also 117 revealed that the TetMESi contained 0.07 wt % residual pyridine and this 118 has relevance to the catalysis of the hydrolysis of TetMESi by water. 119

The structure of the tetramethacrylate, TetMESi, is analogous to the dimethacrylate, diethylene glycol dimethacrylate (DEGDMA, supplied by Sartomer USA), in that the mass per methacrylate unit is similar (121 g/mol of methacrylate units in DEGDMA versus 136 g/mol for TetMESi), and so DEGDMA was chosen for comparison with the silane monomer. TetMESi and DEGDMA were homo- and copolymerized using 0.5 wt % (\pm)-camphorquinone (CQ, supplied by Sigma Aldrich Pty Ltd.) as a visible light photoinitiator and 0.30 wt % *N*,*N*,3,5-tetramethylaniline (TMA, supplied by Sigma Aldrich Pty Ltd.) as photoreducer. The TMA photoreducer and the residual pyridine in the TetMESi synthesis are basic with pK_b (aqueous, 20–25 °C) values of 8.9 for *N*,*N*-dimethylaniline (which is analogous to TMA) and 8.8 for pyridine,²⁶ so that the pH of an aqueous solution of these species should be approximately 9 and so only slightly basic. All chemical structures of the materials used are presented in Scheme 1.

Since NMR studies of the hydrolysis of polymerized TetMESi by water 135 are difficult, we studied the hydrolysis of the monomer in a 70/30 w/w 136 blend of TetMESi and acetone-d₆ (supplied by Cambridge Isotope 137 Laboratories Inc.). The acetone was used as a NMR spin lock and also 138 as a solubilizer for TetMESi and water. To this blend was added 4.63 139 pph water (6.2 wt % water based on the monomer and equal to the 140 stoichiometric amount required for complete hydrolysis). In addition, 141 since the photoinitiation system contained 0.3 wt % TMA as discussed 142 above, which is basic and was expected to catalyze the hydrolysis, this level 143 was added to the TetMESi/acetone blend. A 300 MHz Bruker ¹H NMR 144 was used to monitor the disappearance of the methylene group of TetMESi 145 $(-CH_2-O-Si-)$ at $\delta = 3.9$ ppm and the emergence of the methylene 146 group of HEMA ($-CH_2OH$) at δ = 3.7 ppm. The formation of the silica 147 particles was also monitored by visual observation of the development of 148 turbidity of a water-saturated solution of TetMESi (\sim 1.5 wt %). Schematic 149 2 shows the pathways for polymerization/hydrolysis of TetMESi. 150 S2

The isothermal photopolymerization studies were conducted under a N_2 151 atmosphere at various temperatures from -10 to +90 °C using a differential scanning calorimeter (Perkin-Elmer DSC-7 and Intracooler). 153 The instrument was modified to allow the simultaneous irradiation of the sample pans, as previously discussed by Cook.²⁷ The calorimeter was calibrated for temperature and enthalpy using zinc and indium standards. 156 The DSC sample was irradiated with a broad band dental curing light 157



Scheme 2. Polymerization Pathways of the TetMESi Monomer and Hydrolytic Pathways of the Monomer and Polymer

(Visilux, 3M) which produces visible light with the wavelength ranging 158 from 400 to 500 nm and has a maximum emittance at 470 nm correspond-159 ing to the absorption maximum of CQ. Due to the fast polymerization rate of the monomers with this photocuring source, its intensity was reduced by a factor of 10 by placing a neutral density filter (Schott) between the source and the fiber optic bundle. The irradiation intensity at the surface of the 163 DSC pan was measured using an International Light IL1700 radiometer 164 equipped with a SED033/UVA/W detector and found to be 10.7 mW/ 165 cm². The theoretical heat of polymerization for the methacrylate group 166 $(54.4 \text{ kJ/mol})^{28}$ was used to calculate the conversion of double bonds from 167 the experimental heat of polymerization of the monomers. 168

For the preparation of the cured polymer specimens, the monomer 169 170 blends and initiators were injected between two glass slides separated by a 1.4 mm thick silicone gasket and were photocured at 60 °C by the 171 Visilux source without a filter at an irradiance of 5.1 mW/cm² for 10 min. 172 The samples were then postcured at 120 °C for 2 h. 173

Cured samples of the TetMESi and DEGDMA and their blends 174 were exposed to a water vapor saturated atmosphere at 40 °C and 175 their wt % water uptake (the mass of absorbed water divided by the 176

initial specimen mass) was monitored as a function of time. During the water uptake experiment, the 1.4 mm thick specimens containing TetMESi became cloudy as a result of the hydrolysis of the Si-O-C links and the formation of SiO₂ particles. The progress of the particle formation and thus light scattering was monitored by measurements of the forward scattered ultraviolet-visible radiation using a Varian Cary 300BIO UV-vis spectrophotometer fitted with a DRA-CA-30I sphere accessory. These spectra were measured from 800 to 200 at 600 nm/min and are presented as the percent transmission and the apparent absorption (the logarithm of the inverse fractional transmission) versus the wavelength.

Digital optical photographs of the polymers were taken of 1.4 mm thick samples overlaid on white paper with crisply printed text to highlight the relative transparency of the materials.

The dynamic mechanical properties of the specimens with dimensions of 1.4 mm imes 5 mm imes 40 mm were measured at 1 Hz by a Perkin-Elmer DMA 8000 instrument tested in dual cantilever geometry and using a heating rate of 3 °C/min from -90 to +250 °C. Where it could be clearly defined, the glass transition temperature (T_g) was taken as the temperature at the peak of the tan δ curve.

193

194

195

177

178

179

180



Figure 1. PhotoDSC during the cure of TetMESi with 0.5 wt % CQ and 0.3 wt % TMA at various temperatures.

The Fourier transform infrared spectra of monomers and polymers were recorded using a Nicolet 6700 FTIR spectrometer, with a resolution of 4 cm⁻¹, and a Smart Orbit single-bounce diamond attenuated total reflection (ATR) accessory with a diamond crystal.

RESULTS AND DISCUSSION

F1 201

196

197

198

199

200

Photopolymerization. Figure 1 shows the isothermal photopolymerization behavior of TetMESi at various temperatures, 202 and Table 1 lists the maximum heat flow, heat of polymerization, T1 203 and methacrylate conversion obtained from this data. As com-204 monly found in free radical polymerization, and especially cross-linking systems, $^{27,29-31}$ the rate is initially very slow but rapidly 2.05 206 rises to a maximum and then decreases, due to the combined 207 reduction in the initiation efficiency and the rate of termination 208 by diffusional effects, and the effect of reduction in monomer 209 concentration. The maximum heat flow rises with increased 210 temperature, but a change of 100 °C only causes an increase in 211 rate by a factor of 4. Since the polymerization is photochemically 212 initiated, this rise in polymerization rate with increased tempera-213 ture is probably due to the enhanced rate of propagation.^{27,30,31} 214

Table 1 also shows that the final conversion also increases with 215 raised temperature until a plateau value is achieved, but this 216 maximum value is much less than the full reaction. This type of 217 behavior is commonly observed when the glass transition tem-218 219 perature of the polymerizing monomer/polymer mixture is close to the curing temperature $^{29-33}$ and can be explained as follows. At the 220 221 start of the polymerization, the $T_{\rm g}$ of the monomer is low and so the high molecular mobility in the matrix allows the curing to proceed 222 without hindrance. As the molecular weight and cross-linking in the 223 polymer rises, the glass transition temperature rises, but provided 2.24 the $T_{\rm g}$ is below the curing temperature, the molecular mobility still 225 permits the curing to proceed. When the polymerization causes the 226 227 glass transition to approach the curing temperature, the molecular mobility in the matrix is diminished and so the polymerization rate 228 slows. With further curing, the increase in $T_{\rm g}$ restricts molecular 229 230 mobility and eventually prevents further polymerization. At 231 this stage, the T_{g} attains a plateau value because there is no further 232 increase in molecular weight or cross-link density. If reactive groups still remain at this stage, then polymerization can often 233 be re-established by increasing the curing temperature and thus 234

Table 1. Cure parameters for the Photopolymerization of
TetMESi, DEGDMA, and Their Copolymer at Various
Isothermal Curing Temperatures

	peak maxir	num			
temperature (°C)	heat flow (W/g)	time (s)	$\Delta H (J/g)$	conversion (%)*	
TetMESi					
-10	1 37	72	120	30	
10	1.89	74	142	35	
30	2.52	73	195	48	
50	3.68	73	207	52	
70	5.27	73	243	61	
90	5.56	74	255	64	
	0.00		-00		
50/50 TetMESi/DEGDMA					
-10	1.48	77	137	32	
10	2.37	67	171	40	
30	3.16	71	237	56	
50	4.20	76	235	55	
70	5.93	77	245	58	
90	6.01	75	236	56	
DEGDMA					
-10	0.40	78	110	24	
10	0.62	75	186	41	
30	0.72	188	168	37	
50	1.43	151	207	46	
70	1.66	129	170	38	
90	2.42	115	204	45	

increasing molecular mobility. As a result, the plateau T_g is 235 closely related to the curing temperature. In the case of a 236 monofunctional monomer polymerizing into a linear polymer, 237 the topological ability of a growing chain to react with a 238 monomer is high and so if the curing temperature exceeds 239 the maximum attainable T_{g} , then nearly 100% conversion of 240 monomer to polymer can be achieved. However, in most 241 polymer networks, a high level of cross-linking can impose 242 topological restrictions on the neighboring monomer units or 243 of propagating chains and prevent the conversion from exceed-244 ing a certain limit,^{30,32,34-36} and this is termed the topological 245 limit. Thus the cure temperature and the attainable glass 246 temperature are coupled until either the material is fully cured 247 or topological restrictions prevent further reaction, whereupon 248 the T_{g} becomes independent of further increases in curing 249 temperature, as demonstrated in Table 1 and Figure 1. 250

Photocuring behavior similar to that shown in Figure 1 was 251 observed for the 50:50 copolymer of TetMESi and DEGDMA 252 and for the homopolymerization of DEGDMA, and the curing 253 parameters are listed in Table 1. Figure 2 compares the iso-254 F2 thermal photocuring behavior of TetMESi, DEGDMA, and the 255 copolymer at 50 °C. It is interesting to note that the rate of 256 polymerization of DEGDMA is much less than that for TetMESi, 257 which is less than that for 50:50 TetMESi:DEGDMA. This 258 unusual trend was also observed for these systems at all tem-259 peratures between -10 and +90 °C and may be a result of the 260 effect of two opposing factors on the rate: radical diffusion and 261 the relative reactivity of the methacrylate groups. In a free radical 262 cross-linking system, the rate of translational and segmental 263

282

283

284

285

2.86



Figure 2. PhotoDSC of TetMESi, 50/50 and DEGDMA and copolymers at 50 $^\circ\text{C}.$



Figure 3. ATR-FTIR of DEGDMA and TetMESi monomers (a and b, respectively) and of TetMESi photocured at 60 °C/10 min (c) or 60 °C/10 min and postcured at 120 °C/2 h (d), and of TetMESi cured at 60 °C/10 min and postcured 120 °C/2 h followed by exposure to a water saturated atmosphere for 2 weeks (e).

diffusion of the radicals is reduced as the polymerization 264 proceeds^{30,36-38} and so the rate constant for termination de-265 creases dramatically during the reaction and particularly at the 266 stage of gelation. The monomer that has the higher number of 267 functional groups, TetMESi, should gel at a lower conversion than 268 DEGDMA, and this should cause an earlier and more dramatic 269 reduction in the termination rate and thus a higher polymerization 270 rate of the TetMESi/DEGDMA blend compared with DEGDMA. 271 However, the reactivity of the methacrylate groups in TetMESi 272 may be less than those on DEGDMA and this may cause the 273 decrease in rate of TetMESi compared with the TetMESi/ 274 DEGDMA blend, as is observed in Table 1. 275

Table 1 also reveals that the maximum conversion is higher for TetMESi and the 50:50 blend than for DEGDMA. This is somewhat surprising since the DEGDMA is difunctional while TetME-Si is tetrafunctional and so it might be expected that topological restrictions in the final stages of reaction would be more important for the latter. One explanation for this behavior is that the



Figure 4. Water vapor uptake of the polymers formed from TetMESi, DEGDMA, and their copolymers at 40 °C. The inset shows the variation of the equilibrium water uptake versus composition.

additional flexibility of the -O-Si-O- bond in the TetMESi allows the methacrylate additional ability for reaction, in the same manner that the presence of the additional ethylene oxide unit in triethylene glycol dimethacrylate provided fewer topological restrictions to polymerization compared with DEGDMA.³⁶

Hydrolysis. Figure 3 shows the FTIR ATR spectra of the 287 F3 TetMESi and DEGDMA monomers. Using the functional group 288 characteristic frequencies³⁹ and by comparison of the spectra of 289 TetMESi with DEGDMA, and also other oligo(ethylene glycol) 290 dimethacrylates, it can be concluded that TetMESi exhibits the 291 characteristic peaks at ~2900 (C-H stretch), 1715 (ester carbonyl 292 stretch), 1640 (carbon double bond stretch), 1160 (ester -C-O-293 CH₂ stretch), 1130 (CH₂-O-Si stretch), 1090 (C-O-Si 2.94 stretch), and 980 cm⁻¹ (C–O–Si stretch). As expected, DEGD-295 MA monomer has a similar spectrum but without the peaks at 980 296 and 1090 cm⁻¹. After photocuring at 60 °C, the vinylidene 297 absorption at 1640 cm^{-1} is greatly reduced and results in ${\sim}62\%$ 298 conversion and with postcuring at 120 °C reaches ~68% conversion, 299 which are consistent with the photo-DSC data in Table 1. As 300 discussed above, the pH of an aqueous solution of the amines 301 present in the polymers prepared with TetMESi is expected to be 302 only slightly basic and so the hydrolysis of the monomer is expected 303 to produce silica-based structures intermediate between particles 304 and a silica network. After the polymer has been exposed to saturated 305 water for 2 weeks at 40 °C, new peaks appear at 3350 cm⁻¹ due to 306 the water swelling the polymer and at 1065 cm⁻¹ due to the 307 Si-O-Si bonds in silica. At the same time, the CH₂-O-Si peak at 308 1130 cm^{-1} disappears due to its hydrolysis while the stretch of the 309 ether link in the ester at 1160 cm^{-1} remains. 310

Water vapor absorption experiments were performed with the 311 polymers of TetMESi, DEGDMA and their blends and the 312 kinetics are given in Figure 4. The polymer of TetMESi absorbed 313 F4 a very high amount of water (approximately 30 wt % uptake) and 314 this can be attributed to the water required (6.2 wt % water) for 315 hydrolysis of the polymer to poly(hydroxyethyl methacrylate), 316 hydroxyethyl methacrylate (HEMA) monomer and silica, plus 317 the amount of water that the poly(hydroxyethyl methacrylate) 318 and HEMA monomer absorbs. Hodge et al.⁴⁰ reported that the 319 water uptake of poly-HEMA was approximately 37 wt % water at 320 25 °C while Dimarco et al.41 obtained 40 wt % (presumably at 321 room temperature) and Kolarik and Janacek⁴² obtained 46 wt % 322 (presumably at room temperature), which is considerably higher 323

Е



Figure 5. Photographs of cured 1.4 mm thick specimens (located at the bottom of the images) on top of a white printed card, indicating the level of transparency of (a) polymerized TetMESi, (b) polymerized TetMESi after hydrolysis with water vapor, and (c) polymerized TetMESi after hydrolysis and drying.



Figure 6. (a) UV-vis data taken with an integrating sphere as the polymerized TetMESi absorbed water and became hazy. (b) UV-vis data taken with an integrating sphere as the polymerized DEGDMA absorbed water but remaining transparent.

than the value determined here. Sideridou and Karabela⁴³ have 324 measured the water uptake of a 31 wt % (50:50 mol %) copolymer 325 of HEMA and triethylene glycol dimethacrylate (which has a 326 structure similar to that of DEGDMA) and obtained a value of 11 327 wt % at 37 °C, which is also higher than the interpolated value of 328 8% obtained from Figure 4. The reason for these differences may be 329 due to two effects. As noted by Kolarik and Janacek,⁴² poly-HEMA 330 swollen in liquid water forms two phases (bound water and free 331 water), and it is possible that our samples do not contain free water 332 because they were saturated by water vapor and not by immersion in the liquid. In addition, D'Agostino et al.⁴⁴ also observed a reduction in 333 334 water absorption with addition of nanosilica particles in poly-HEMA 335 and this effect may apply to our system of poly-HEMA and silica. 336

Figure 4 also shows that the equilibrium water uptake is a nonlinear function of the weight percentage of TetMESi, which is similar to that found by Hodge et al.⁴⁰ for copolymers of HEMA and 2-ethoxyethyl methacrylate.

F5 341 As shown in Figure 5, the specimens of polymerized TetMESi, its hydrolyzed form, and the specimen after redrying are relatively 342 transparent as noted by Kloosterboer and Touwslager²⁰ for the 343 acrylate analogue of TetMESi. However, close inspection of the 344 hydrolyzed polymers did show evidence of a slight haze due to the 345 precipitation of SiO₂ nanoparticles or nanostructures. Assuming full 346 hydrolysis of the polymer, 10 wt % of silica would be formed in the 347 poly(HEMA) matrix. Further evidence of the formation of a separate 348 silaceous phase was obtained from UV-vis spectroscopy by collect-349 ing the transmitted and forward scattered radiation using an integrat-350 ing sphere; these data are shown in Figure 6a and are presented as the F6 351 352 percent of transmitted and forward scattered radiation and as the 353 apparent absorbance (the logarithm of the inverse fractional transmittance). The spectrum for the unhydrolysed silane polymer 354 showed absorptions due to residual levels of the CQ photoinitiator 355

(maximum at 470 nm) and absorption below 400 nm due to residual 356 impurities in the original monomer and in the TMA. Upon exposure 357 to the water vapor, the transmittance decreases predominantly near 358 650 nm and near 420 nm and this is probably due to scattering of the 359 silica nanoparticles or nanostructures.^{45,46} In contrast, the spectra 360 from the DEGDMA polymer (Figure 6b) is virtually unaffected by 361 the absorption of water because no new silica phase is formed. 362 Copolymers of TetMESi with DEGDMA showed spectra midway 363 between that of the two components. 364

The kinetics of formation of the SiO₂ is controlled by the diffusion rate of the water into the polymer matrix and of the rates of hydrolysis of the Si-O-CH₂ groups and condensation reaction of the silanol groups. As shown by the DSC data (Table 1) and the DMTA data presented below, the TetMESi polymer is glassy at room temperature whereas the swollen poly(HEMA) byproduct is rubbery and so water absorption is expected to be slow and via case II diffusion, otherwise known as relaxation-controlled transport,⁴⁷ where the water profile as a function of distance into the specimen is rather square. An approximate measure of the rate of silica formation can be obtained when the change in apparent absorbance, in the region from 550 and 600 nm, is 50% of the total change and for TetMESi this appears to be approximately 50 h based on the data in Figure 6a). This is similar to the time of 37 h for the water absorption to attain 50% of its final value (approximately 900 min or 15 h; see Figure 4) but is considerably greater than the time for 50% hydrolysis of the monomer (see Figure 7), as would be expected because the time for water diffusion in the latter is minimal.

Dynamic Mechanical Thermal Analysis. The DMTA of the
polymers from TetMESi, DEGDMA and the 50/50 copolymer
are shown in Figure 8. In all cases, the glass transition region is
very broad and the modulus remains high up to 250 °C. The tan
 δ is also seen to be very low, and the maximum tan δ is only383
384
385

365

366

367

368

369

370

371

372

373

374

375

376

377

378

379

380

382

381 F7



Figure 7. Kinetics of hydrolysis of the TetMESi monomer at 25 °C in a 70/30 mixture of TetMESi/acetone and 0.3 wt % TMA, and containing the stoichiometric amount of water required for hydrolysis.



Figure 8. DMTA of the polymers from TetMESi, DEGDMA, and the 50/50 copolymer. Data points have been removed to improve the clarity of the figure.

0.055-0.07, which is approximately one-tenth of that normally 388 observed with linear and lightly cross-linked polymers. This 389 behavior is probably due to the small amount of molecular 390 391 movement available in the network structure which reduces the intersegmental friction.48,49 392

During water uptake, specimens containing TetMESi became 393 soft as a result of the hydrolysis of the Si-O-C links, which 394 reduced the cross-link density and also due to the hydro-395 plasticization of the polymer. Figure 9 shows this behavior for F9 396 the hydrolyzed and water-saturated material. The tan δ curve 397 shows a maximum corresponding to the inflection in the 398 modulus curve at approximately 30 °C and a corresponding 399 maximum in G'' at -10 °C, apparently due to the glass transition 400 of the water vapor-saturated poly-HEMA polymer. This is in 401 agreement with the data of Kolarik and Janacek⁴² who reported a 402 maximum in G'' (1 Hz) near -10 °C in water-saturated (46% 403 water uptake) due to the glass transition. However, the drop in 404 the real modulus curve in Figure 9 is very broad and at 405 approximately 105 °C another tan δ maximum is observed. This 406 is due to the effect of water evaporation from the wet poly-HEMA 407 sample during the DMTA experiment, which causes the specimen 408



Figure 9. DMTA of polymerized TetMESi: (1) after equilibrium exposure to saturated water vapor, (2) after repeating the DMTA test on the same sample, and (3) after repeating the DMTA test on an identical sample after drying under vacuum at 60 °C for 24 h. Data points have been removed to improve the clarity of the figure.



Figure 10. DMTA of copolymerized 50/50 TetMESi/DEGDMA: (1) as a dry sample, (2) after equilibrium exposure to saturated water vapor, and (3) after redrying under vacuum at 60 °C for 24 h. Data points have been removed to improve the clarity of the figure.

to vitrify (especially in the outer surfaces of the flexural specimen 409 that contribute most to the overall DMTA behavior) and thus exhibit a second glass transition of the dry poly-HEMA; the modulus data do not show a corresponding change in slope, but this may be obscured by the apparent breadth of the overall transition. This explanation is confirmed by a subsequent rescan of the same specimen in the DMTA; in this second test the low 415 temperature tan δ peak is absent and only a broad curve with a 416 peak near 105 °C is observed. When an identical specimen, which 417 had been fully hydrolyzed and hydrated, was then dried under 418 vacuum at 60 °C for 24 h, a much sharper tan δ curve was observed 419 with the tan δ peak shifted to the higher temperature of 114 °C 420 and a maximum in the loss modulus at 90 °C. These values are 421 similar to that of 109 °C (tan $\delta_{\rm max}$ 0.3 Hz) found by Dimarco 422 et al.⁴¹ and that of 110 °C (G_{max} , 1 Hz) by Kolarik and Janacek⁴² 423 for dry poly-HEMA. 424

Similar behavior was observed for the 50:50 wt % copolymer of TetMESi and DEGDMA (see Figure 10). Here, the highly cross-linked, unhydrolyzed copolymer had a broad transition 425

426 F10

with little change in modulus and low tan δ . On hydrolysis the 428 42.9 tan δ increased significantly due to the greater amount of molecule movement available in the less highly cross-linked 430 material, as discussed above, and three transitions appear to be 431 present due to the effect of water loss changing the viscoelastic 432 behavior of the polymer as the temperature increases. In addi-433 tion, the storage modulus shows a larger decrease and the 434 435 existence of a rubbery plateau due to the fewer cross-links in 436 the copolymer. When this hydrolyzed polymer was redried, the damping behavior is dominated by one main glass transition at 437 about 160 °C due to the dry copolymer of HEMA and DEGD-438 MA. In contrast, the viscoelastic behavior of the water-saturated 439 poly-DEGDMA specimen and of this specimen after drying was 440 similar to that for the virgin material shown in Figure 8 because 441 its structure is not significantly affected by water absorption. 442

CONCLUSIONS

443

465

466

467

476

The rate and final conversion of isothermal photopolymeri-444 zation kinetics of a tetramethacrylate silane (TetMESi) mono-445 mer and its copolymerization with diethylene glycol 446 dimethacrylate increase with raised curing temperature due to 447 its effect on the propagation rate constant and the molecular 448 mobility of the networks but full conversion is not attained due to 449 topological restrictions on the methacrylate groups or chain 450 radicals. The resulting materials have glass transition regions of 451 low damping and with breadths of over 200 °C. In addition, the 452 modulus of the materials does not show an abrupt drop in the 453 glass transition and at 200 °C it is still above 0.5 GPa. 454

As confirmed by NMR studies of the monomer and FTIR 455 studies of the polymer, exposure of poly-TetMESi to water vapor 456 slowly causes hydrolysis of the Si-O-CH₂ bonds and water 457 sorption studies show that poly-TetMESi absorbs \sim 30% water at 458 equilibrium due partly to the consumption of water in the 459 hydrolysis reaction but primarily due to swelling of the poly-460 HEMA. As a result of this, the dynamic mechanical properties of 461 the hydrolyzed polymers were changed dramatically and the T_{g} 462 reduced by water plasticization and loss of cross-links but drying 463 464 of these polymers raised the T_{σ} again.

Absorption of water by polymers containing TetMESi also caused the production of nanoscale particles or structures, as observed by the appearance of scattering in the UV-vis spectra.

From these results it may be concluded that these types 468 of silicon-containing polymers may be useful for relatively 469 transparent, low damping, high temperature, but anhydrous, 470 applications or for cross-linked adhesives which require high 471 modulus initially but which loose stiffness on exposure to water. 472

AUTHOR INFORMATION 473

474 **Corresponding Author**

*E-mail: wayne.cook@eng.monash.edu.au. 475

Notes 477

^{\perp}Here the term "functional group" means the reactive group on 478 479 the monomer molecule and "multifunctional" means a monomer with more than one fuctional group. 480

ACKNOWLEDGMENT 481

482 We acknowledge the financial support by the Australian Research Council Discovery Grant DP1093217 for research 483 funding and for travel support for M.U. to Monash University, 484

493

494

495

496

497

498

499

500

501

502

503

504

505

506

507

508

509

510

511

530

531

532

533

534

535

536

537

538

539

540

541

542

543

544

545

546

547

548

and we also express appreciation for a Monash 2009 European Travel Grant which facilitated the visit of M.S. to Monash University.

REFERENCES

(1) Sanchez, C.; Ribot, F. New J. Chem. 1994, 18, 1007-1047.

(2) Tan, B.; Pan, H. M.; Irshad, H.; Chen, X. H. J. Appl. Polym. Sci. 2002, 86, 2135-2139.

(3) Park, H. S.; Yang, I. M.; Wu, J. P.; Kim, M. S.; Hahm, H. S.; Kim, S. K.; Rhee, H. W. J. Appl. Polym. Sci. 2001, 81, 1614-1623.

(4) Priola, A.; Gozzelino, G.; Ferrero, F. Int. J. Adhes. Adhes. 1990, 10.77-80.

(5) Pope, E. J. A.; Mackenzie, J. D. J. Non-Cryst. Solids 1986, 87, 185-198.

(6) Buckley, A. M.; Greenblatt, M. J. Chem. Educ. 1994, 71, 599-602. (7) Brinker, C. J.; Scherer, G. W. Sol-gel science: the physics and

chemistry of sol-gel processing; Academic Press: Boston, 1990; Part 1, p 112.

(8) Schubert, U.; Hüsing, N. Synthesis of inorganic materials, 2nd ed.; Wiley-VCH: Weinheim; New York, 2004; Chapter 4.

(9) McCormick, A. Recent progress in the study of the kinetics of sol-gel SiO2 synthesis reactions. In Sol-Gel Processing and Applications; Attia., Y. A., Ed.; Plenum Press: New York., 1994.

(10) Brinker, C. J.; Clark, D. E.; Ulrich, D. R. Symposium on Better Ceramics Through Chemistry II Held in Palo Alto, California. on April 15-19, 1986; Materials Research Society: Pittsburgh, PA, 1986; Vol. 73.

(11) Novak, B. M.; Davies, C. Macromolecules 1991, 24, 5481-5483. (12) Ellsworth, M. W.; Novak, B. M. J. Am. Chem. Soc. 1991, 113, 2756-2758.

(13) Novak, B. M. Adv. Mater. 1993, 5, 422–433.

(14) Wei, Y.; Yang, D. C.; Bakthavatchalam, R. Mater. Lett. 1992, 13.261-266.

(15) Davidson, R. S.; Ellis, R.; Tudor, S.; Wilkinson, S. A. Polymer 1992, 33, 3031-3036.

(16) Batten, R. J.; Davidson, R. S.; Ellis, R. J.; Wilkinson, S. A. Polymer 1992, 33, 3037-3043.

(17) Novak, B. M.; Ellsworth, M. W. Mater. Sci. Eng., A 1993, 162.257-264.

(18) Wei, Y.; Wang, W.; Yang, D. H.; Tang, L. G. Chem. Mater. 1994, 6, 1737-1741.

(19) Novak, B. M.; W., E. M.; Verrier, C., Nanostructured Organic Inorganic Hybrid Materials Synthesized Through Simultaneous Processes. In Hybrid Organic-Inorganic Composites: American Chemical Society: Washington, DC, 1995; Vol. 585, pp 86-96.

(20) Kloosterboer, J. G.; Touwslager, F. J. Method of preparing a composite material of silica network and chains of a polyhydroxy compound and a liquid crystal display device incorporating such composite material. US Patent 5437896-A, 1995.

(21) Wei, Y.; Jin, D. L.; Yang, C. C.; Wei, G. J. Sol-Gel Sci. Technol. 1996, 7, 191-201.

(23) Spange, S.; Grund, S. Adv. Mater. 2009, 21, 2111-2116.

(24) Innocenzi, P.; Brusatin, G.; Guglielmi, M.; Bertani, R. Chem. Mater. 1999, 11, 1672–1679.

(25) Matejka, L.; Dusek, K.; Plestil, J.; Kriz, J.; Lednicky, F. Polymer 1999, 40, 171-181.

(26) Weast, R. C.; Chemical Rubber, C. Handbook of chemistry and physics: a ready-reference book of chemical and physical data; CRC Press: Cleveland, OH, 1973.

(27) Cook, W. D. Polymer 1992, 33, 600-609.

(28) Tong, L. K. J.; K., W. O. J. Am. Chem. Soc. 1945, 67, 1278-1281.

(29) Horie, K.; Hiura, H.; Sawada, M.; Mita, I.; Kambe, H. J. Polym.

- Sci., Part A: Polym. Chem. 1970, 8, 1357-1372.
 - (30) Cook, W. D. Polymer 1992, 33, 2152-2161.

(31) Scott, T. F.; Cook, W. D.; Forsythe, J. S. Polymer 2002, 43, 5839-5845.

549 550

(22) Yoshinaga, I.; Katayama, S. J. Sol-Gel Sci. Technol. 1996, 6.151-154.

559

560

- 551 (32) Rozenberg, B. A. Adv. Polym. Sci. 1986, 75, 113–165.
- 552 (33) Wisanrakkit, G.; Gillham, J. K. J. Coat. Technol. 1990, 62, 35–50.
- 553 (34) Loshaek, S.; Fox, T. G. J. Am. Chem. Soc. 1953, 75, 3544–3550.
- 554 (35) Oleinik, E. F. Adv. Polym. Sci. 1986, 80, 49–99.
- (36) Cook, W. D. J. Polym. Sci., Part A: Polym. Chem. 1993,
 31, 1053–1067.
- (37) Soh, S. K.; Sundberg, D. C. J. Polym. Sci., Part A: Polym. Chem.
 1982, 20, 1299–1313.
 - (38) Stickler, M. Macromol. Chem. Phys. 1983, 184, 2563-2579.
 - (39) Socrates, G. Infrared and Raman Characteristic Group Frequen-
- cies Tables and Charts, 3rd ed.; John Wiley and Sons Ltd.: New York,2001.
- (40) Hodge, R. M.; Simon, G. P.; Whittaker, M. R.; Hill, D. J. T.;
 Whittaker, A. K. J. Polym. Sci., Part B: Polym. Phys. 1998, 36, 463–471.
- (41) Dimarco, G.; Lanza, M.; Pieruccini, M. Nuovo Cimento Soc. Ital.
 Fis., D **1994**, *16*, 849–854.
- 567 (42) Kolarik, J.; Janacek, J. J. Polym. Sci., Part B: Polym. Phys. 1972,
 568 10, 11–22.
- 569 (43) Sideridou, I. D.; Karabela, M. M. J. Appl. Polym. Sci. 2008,
 570 109, 2503–2512.
- (44) D'Agostino, A.; Colella, M.; De Rosa, M.; De Rosa, A.; Lanza,
 A.; Schiraldi, C. J. Polym. Res. 2009, 16, 561–567.
- 573 (45) Bohren, C. F.; Huffman, D. R. Absorption and scattering of light
 574 by small particles; John Wiley and Sons: New York, 1983.
- 575 (46) Zhou, S. X.; Wu, L. M.; Sun, J.; Shen, W. D. Prog. Org. Coat.
 576 2002, 45, 33–42.
- 577 (47) Alfrey, T. G., E.F.; Lloyd, W. G. J. Polym. Sci., Part C: Polym. Lett.
 578 1966, 12, 249–261.
- (48) Andrady, A. L.; Sefcik, M. D. J. Polym. Sci., Part B: Polym. Phys.
 1983, 21, 2453–2463.
- 581 (49) Sauer, J. A. J. Polym. Sci., Part C: Polym. Lett. 1971, 32, 69–122.

ARTICLE